ABSTRACT

An electrostatic chuck is provided which is arranged that, at the time of performing processing treatments of irradiating light to a to-be-processed substrate while holding the translucent to-be-processed substrate, the to-be-processed substrate can surely be held even in case the attraction force lowers due to photoelectric effect. An electrostatic chuck 6 has a chuck plate 61 made of a dielectric material, and a first electrode 63_1 and a second electrode 63_2, both electrodes being disposed in the chuck plate 61. A voltage is applied between the first and the second electrodes 63_1, 63_2 to thereby attract the to-be-processed substrate S to the surface of the chuck plate 61. The electrostatic chuck has, on part of the surface of the chuck plate 61, a substrate holding section 64 which is made of an adhesive sheet and the like having an adhesive force with respect to the to-be-processed substrate S.